

ABSTRACT OF THE DISCLOSURE
DETECTION APPARATUS, EXPOSURE APPARATUS, AND ARTICLE
MANUFACTURING METHOD

A detection apparatus for detecting a plurality of marks arranged on a substrate is provided. The apparatus includes a stage which supports the substrate, a plurality of detectors arranged apart from each other and configured to detect different marks of the plurality of marks arranged on the substrate, and a processor. For each of predetermined combinations of the detectors, the processor inclines a reference member supported by the stage at an inclination according to information on a position of a detection region and a focal position of each detector, and aligns a reference mark arranged on the reference member with each detector, and the processor obtains a measurement offset value of each of the plurality of detectors based on measurement values each acquired by the alignment performed for each of the plurality of predetermined combinations.

(Figure 1)